

One-step electrodeposition of nickel phosphide for enhanced supercapacitive performance using 3-mercaptopropionic acid

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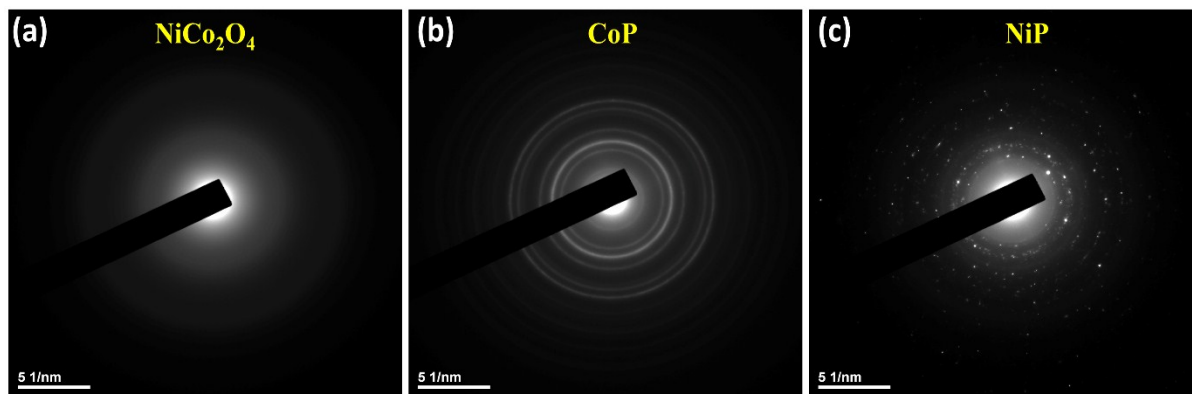


Fig. S1. Selected area electron diffraction (SAED) patterns of NiCo₂O₄, CoP, and NiP via electrodeposition technique.

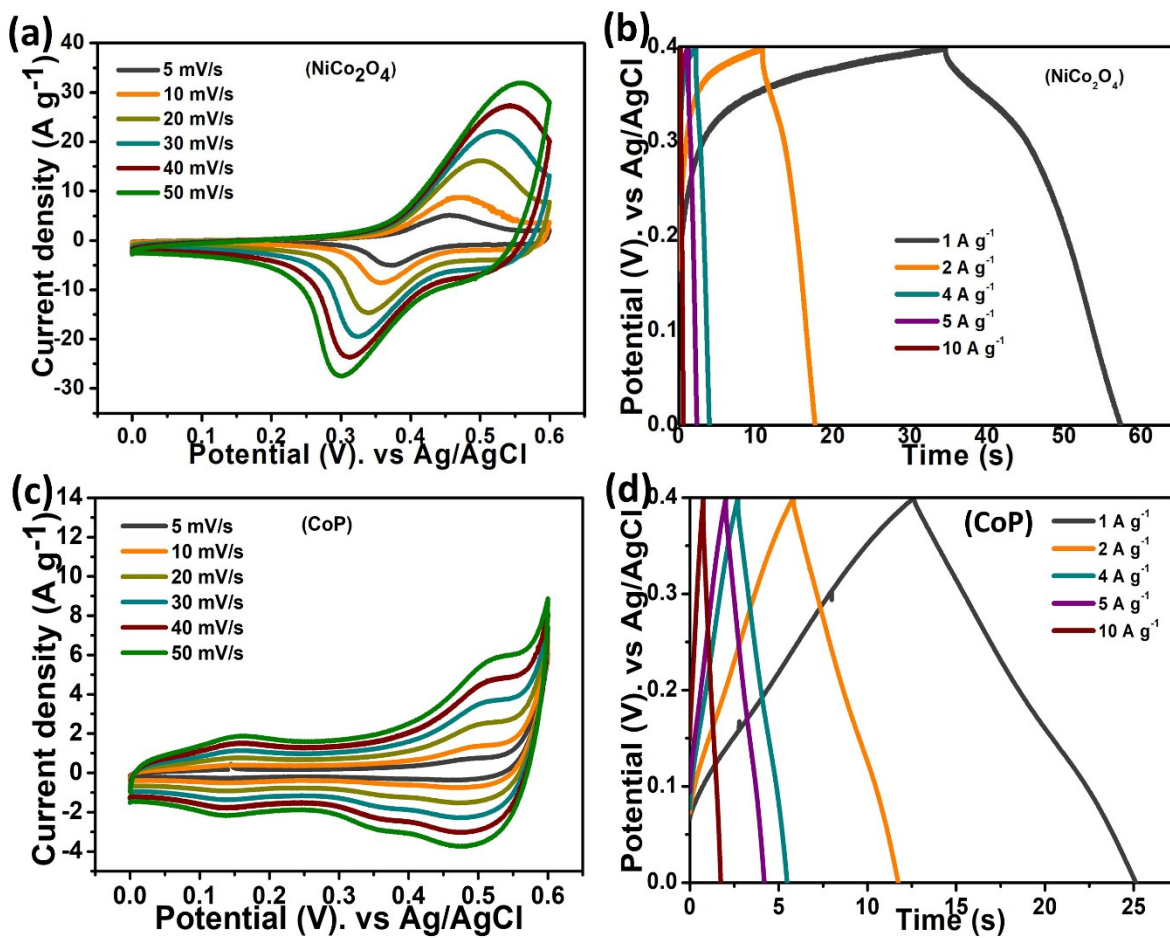


Fig. S2. CV and GCD plot of nickel cobalt oxide (NiCo₂O₄) and cobalt phosphide (CoP) at different scan rates and current densities.

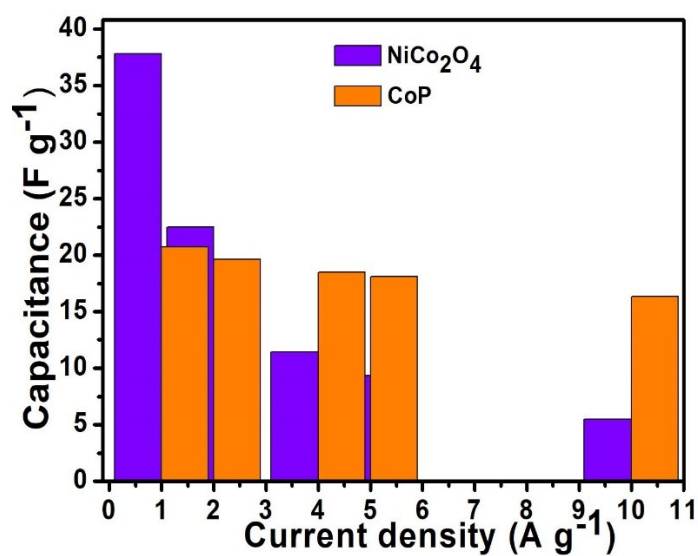


Fig. S3. NiCo₂O₄ and CoP specific capacitance vs current density of NiCo₂O₄ and CoP at various current densities.